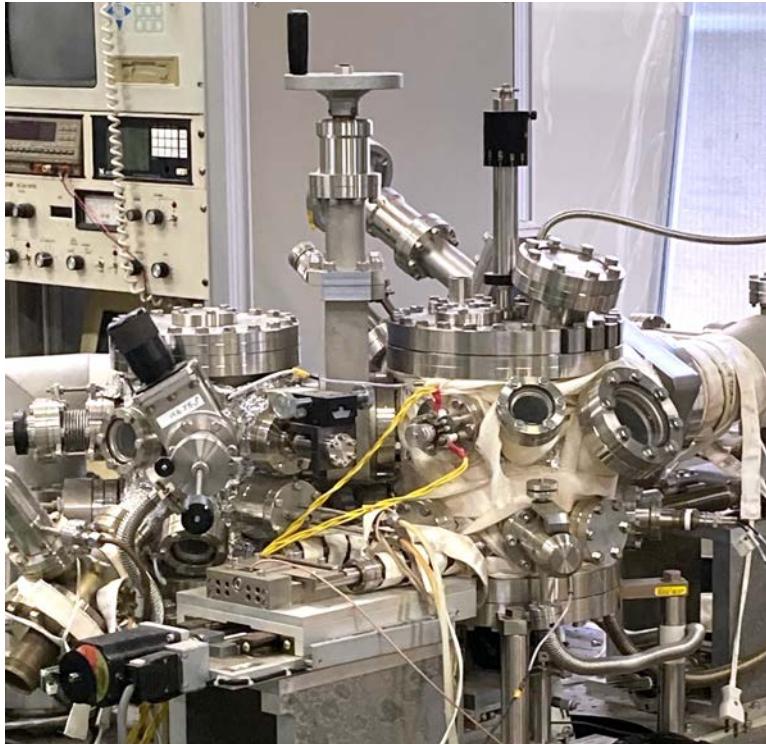


研究紹介

安藤研究室

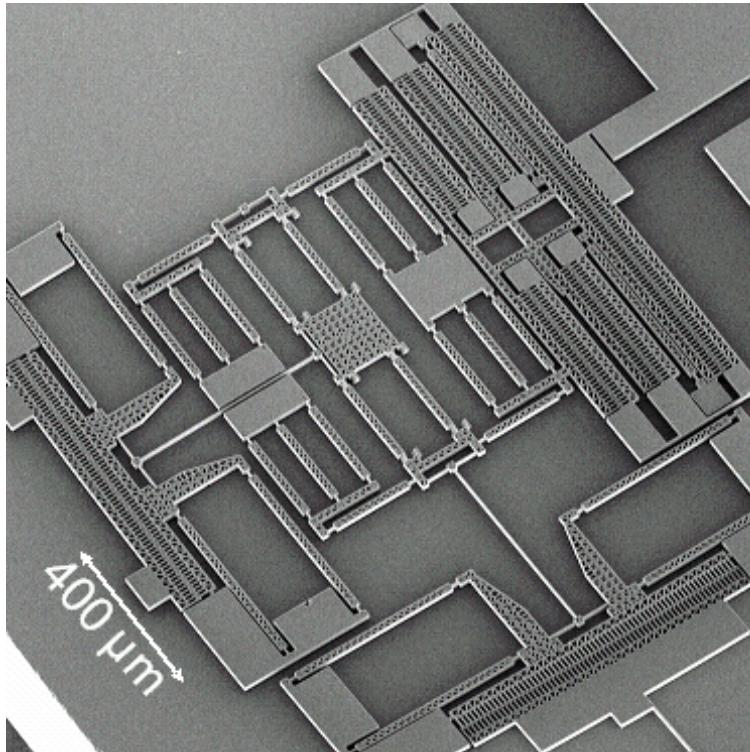
2つの主要テーマ

マイクロ／ナノトライボロジー



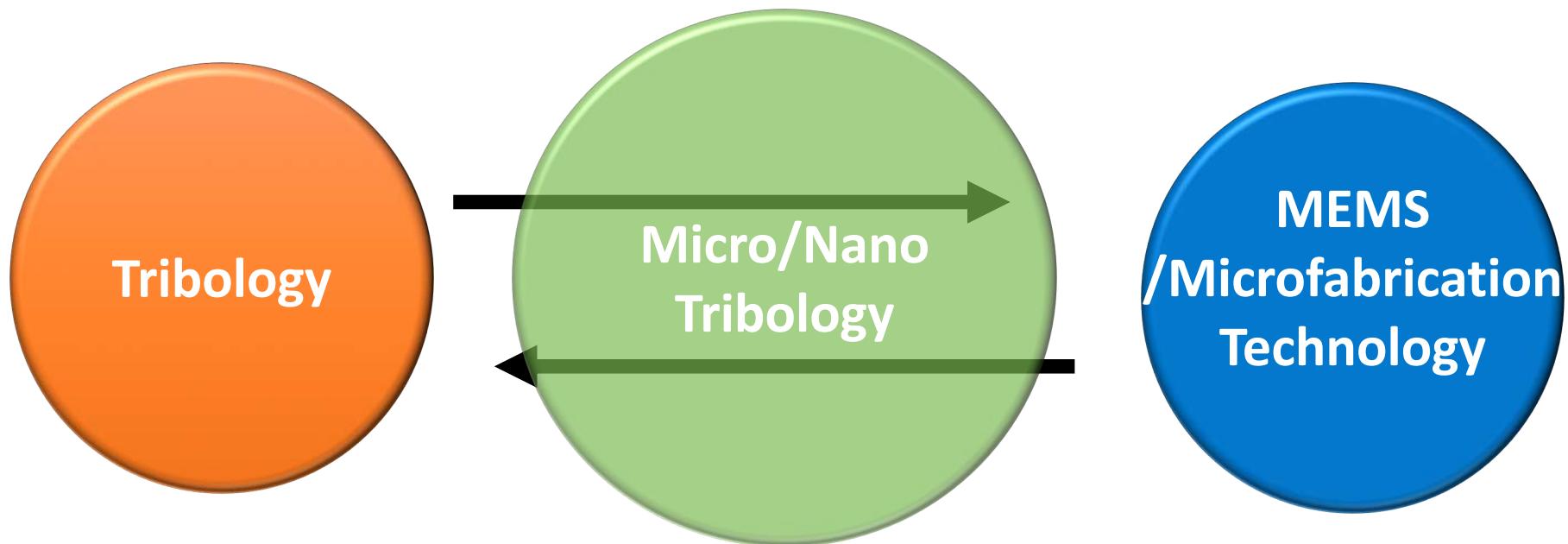
ナノストライプ表面
凝着力
AFM（原子間力顕微鏡）
マイクロ/ナノ表面パターニング
分子動力学計算
流体計算

MEMS及び関連技術



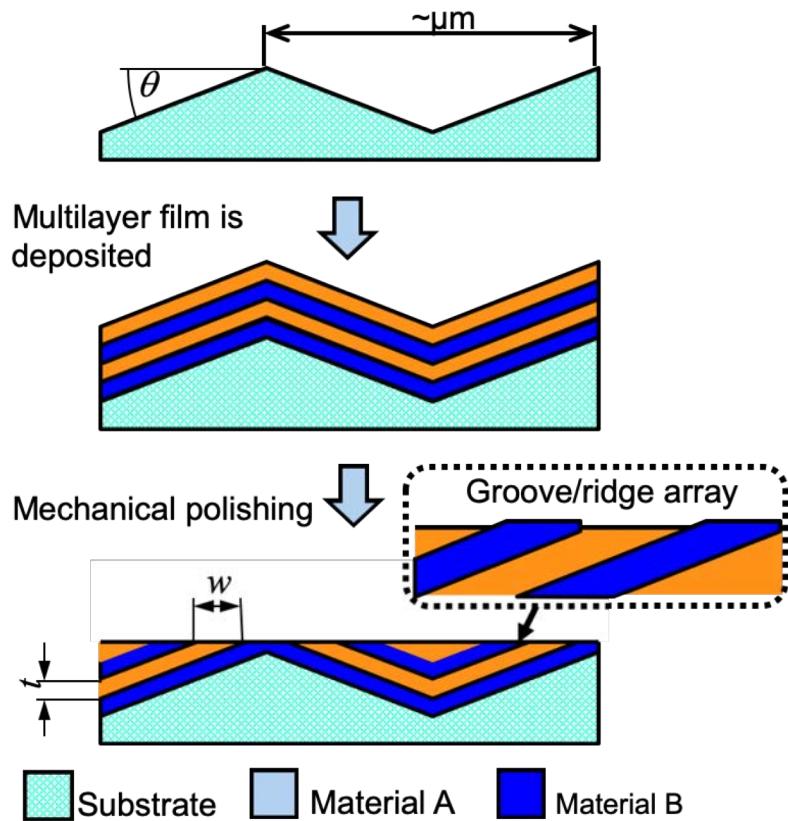
3次元マイクロステージ
AFM組み込みMEMSサンプル
フォトリソグラフィー
結晶異方性エッチング
DRIE (deep reactive ion etching)
集束イオンビーム

新しい分野創出を目指す2つの研究分野

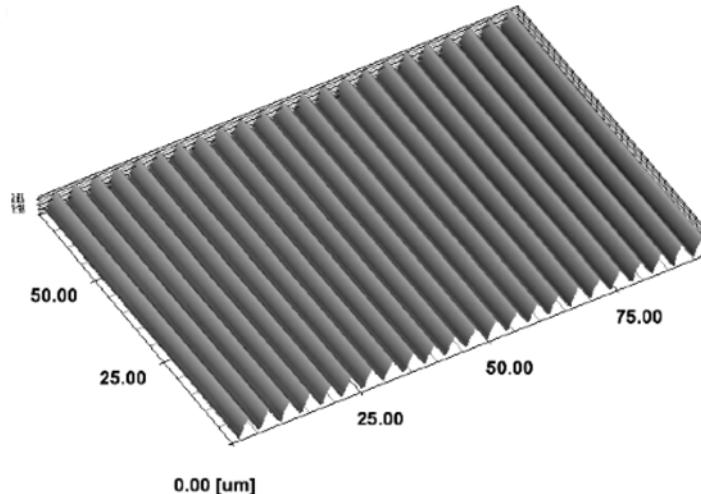


研究テーマの例

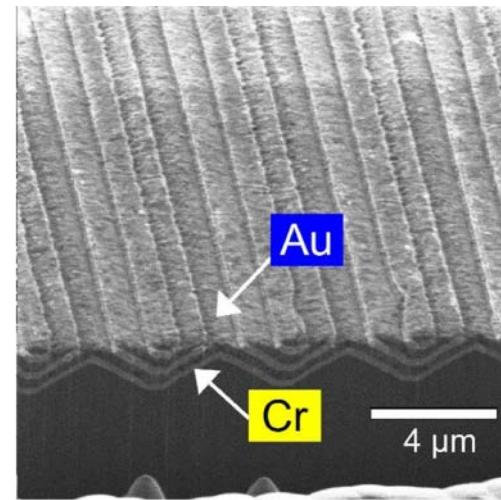
ナノストライプの加工法



ナノストライプ作製法の概要

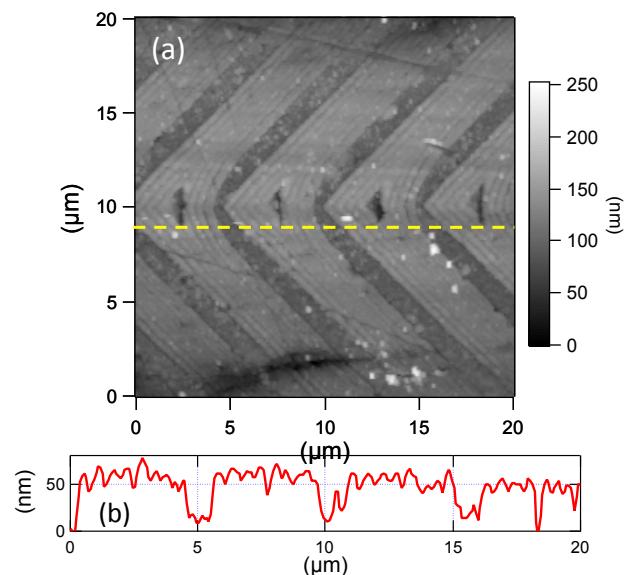
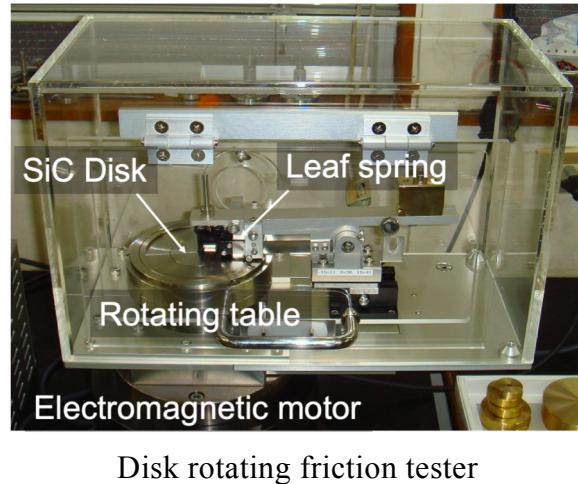
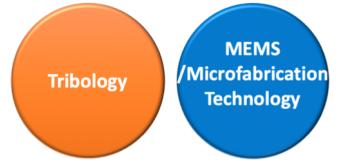


Si(100)面上に結晶異方性エッティングで作製した
周期的傾斜構造（レーザ顕微鏡で計測）

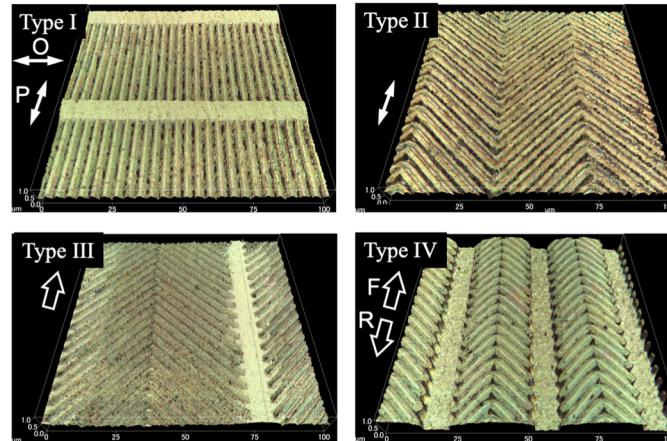


2種類の金属からなるナノストライプ構造の断面

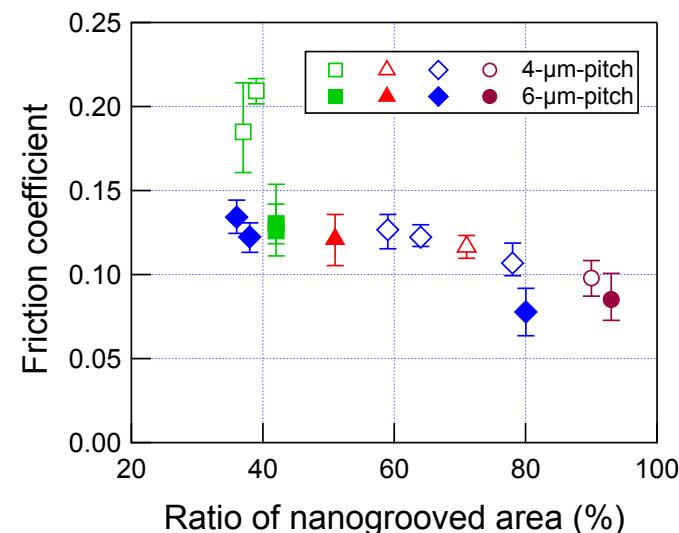
ナノストライプの潤滑特性(1)



摩耗した領域にもナノ溝が残っている

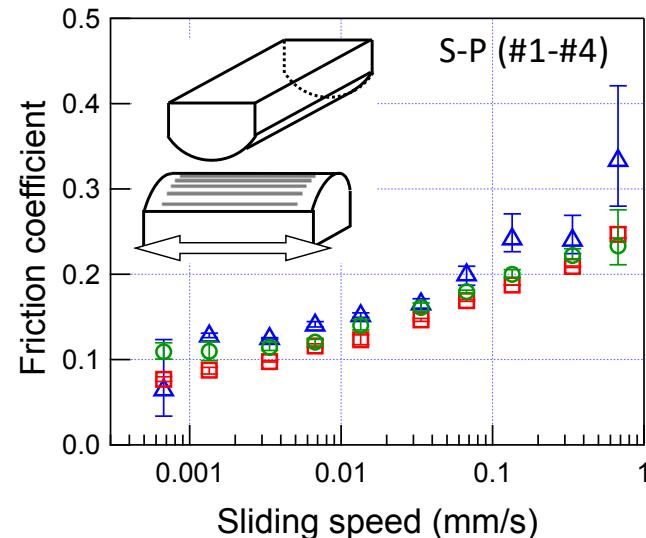
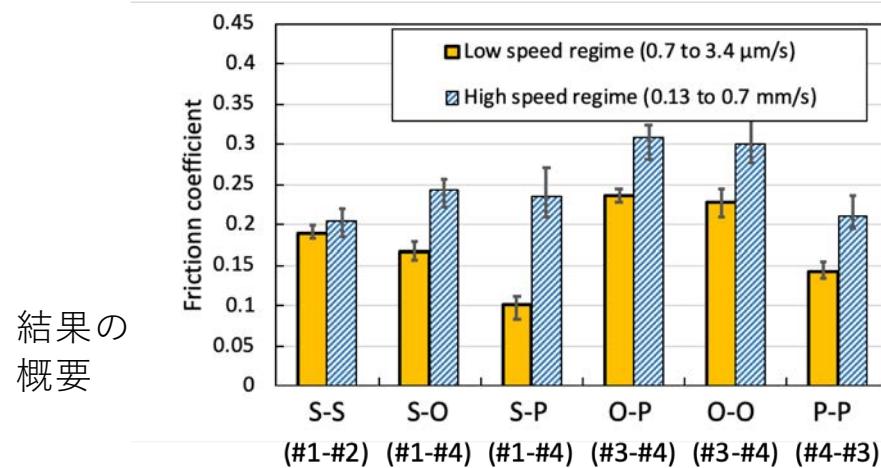
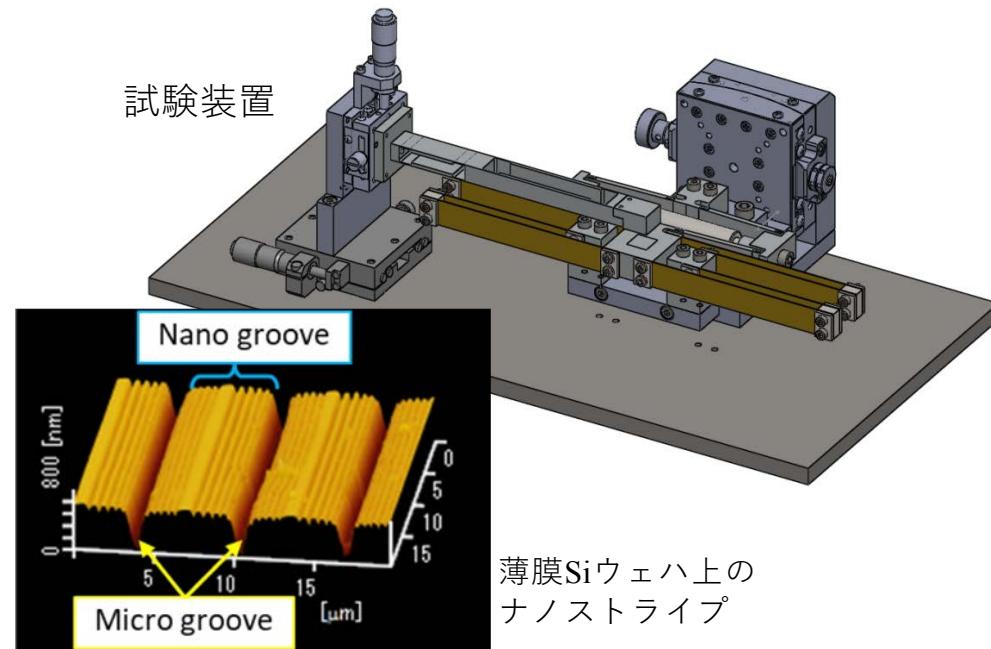
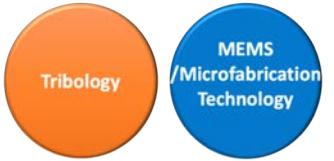


実験に用いた4種類のナノストライプ構造

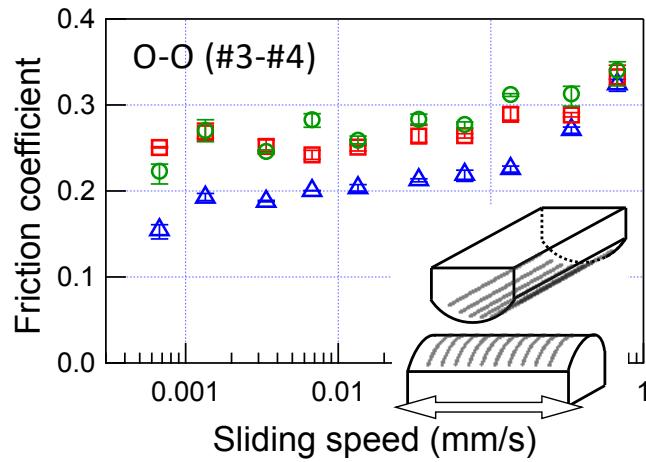


低速ではナノ溝が摩擦係数を低下させる
Type I(□, ■), Type II(△, ▲), Type III(◇, ◆), Type IV(○, ●)

ナノストライプの潤滑特性(2)

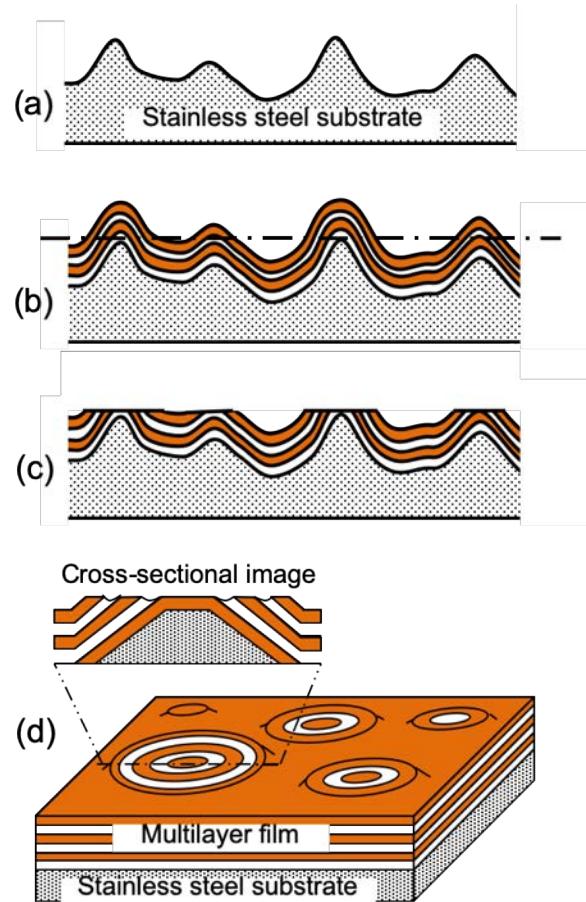


最も低い摩擦係数を示す組合せ

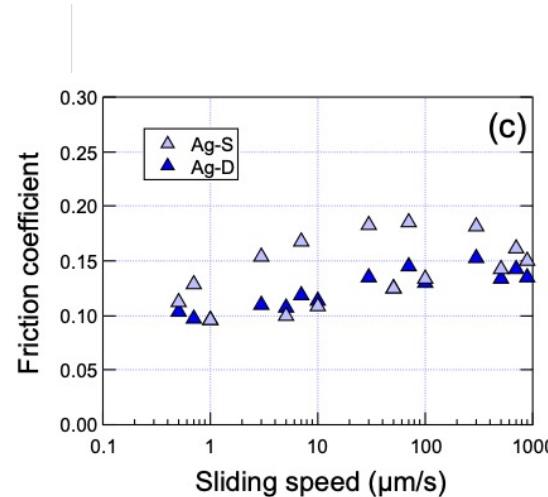


最も高くほぼ一定の摩擦係数を示す組合せ

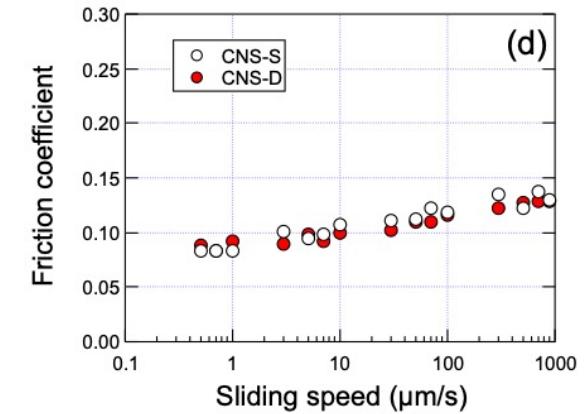
等高線型ナノストライプの潤滑特性



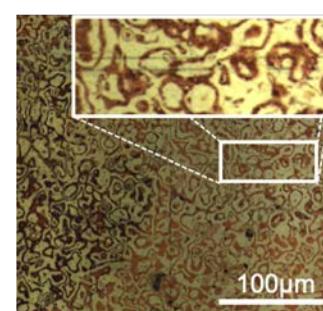
(a) formation of random dents and asperities by shot blasting, (b) formation of multilayer films, (c) polishing of surface, and (d) generation of contoured groove/ridge pattern.



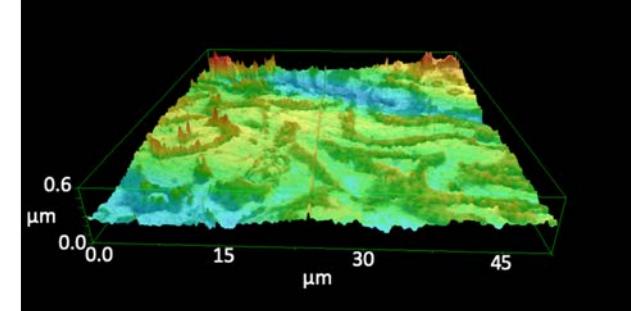
Ag-coated surfaces showed unstable friction coefficient



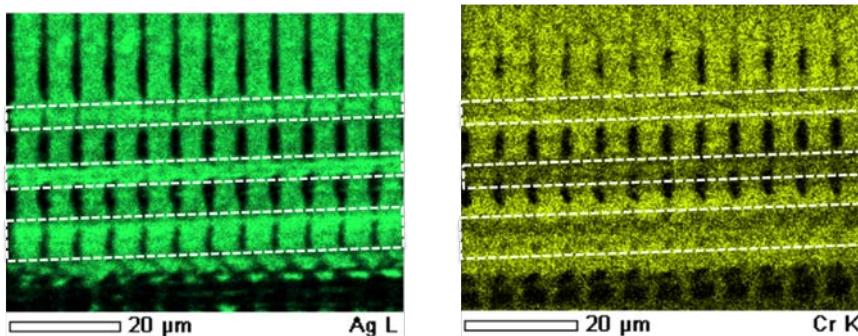
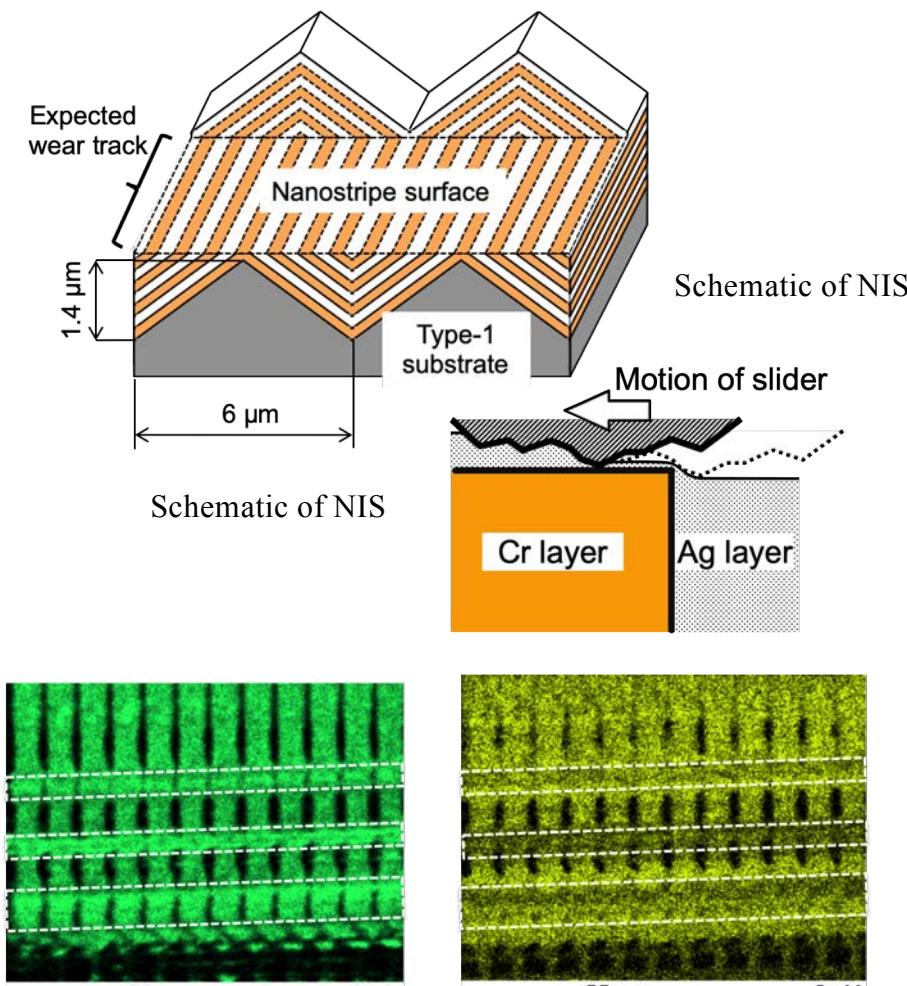
CNS surface showed lowest friction coefficient



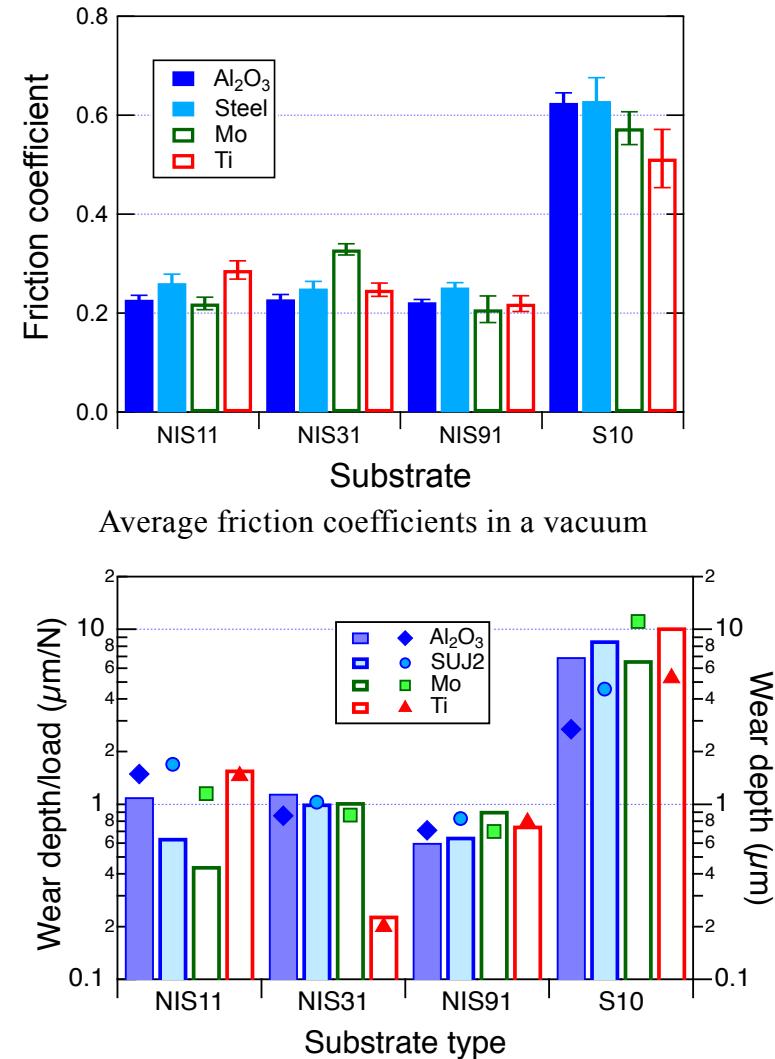
CNS-D substrates observed after friction tests. Nanoscale ridges remained in the wear scar



ナノストライプ誘導構造の乾燥摩擦特性

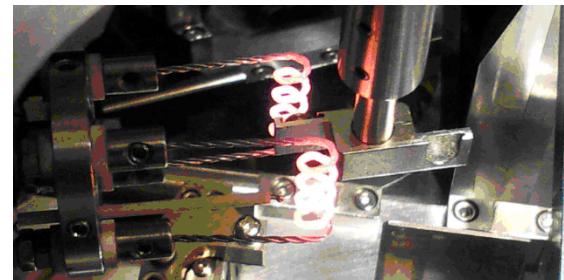
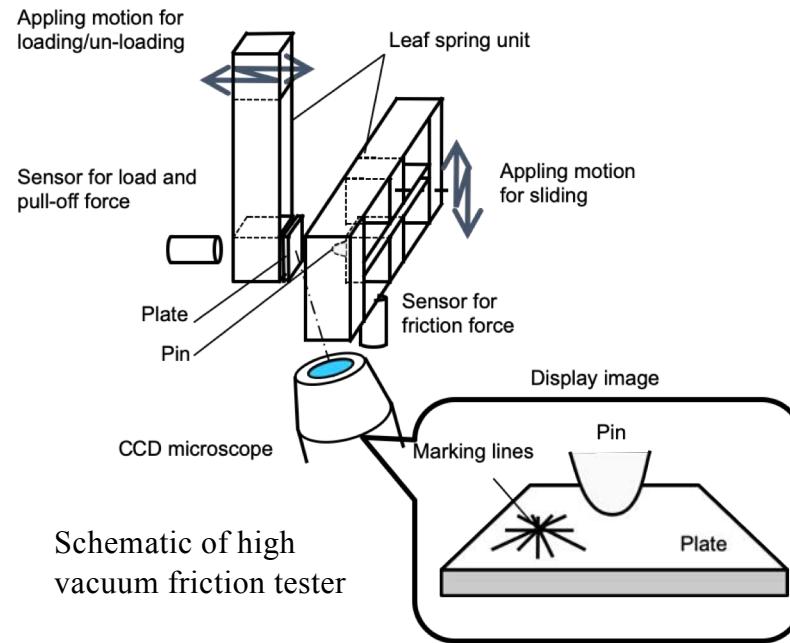


SEM-EDX results for NIS11 rubbed with Al_2O_3

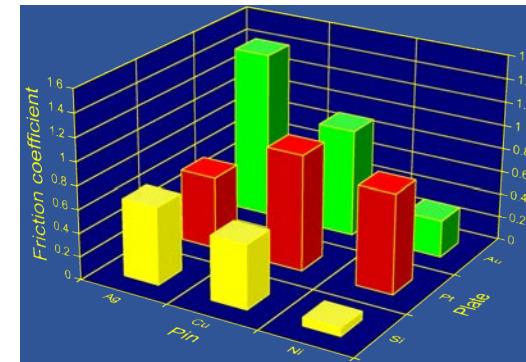


Wear scar depths (symbols) and wear rate (bars)

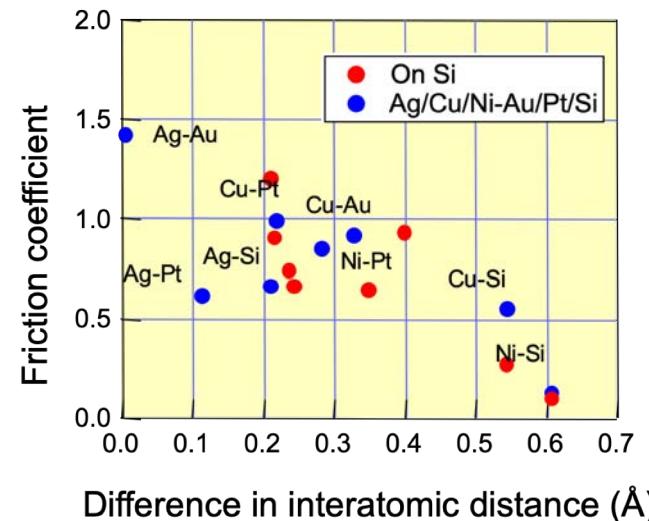
原子間隔差が摩擦係数に及ぼす影響



Test pieces were heated to remove moisture on the surface before measurements

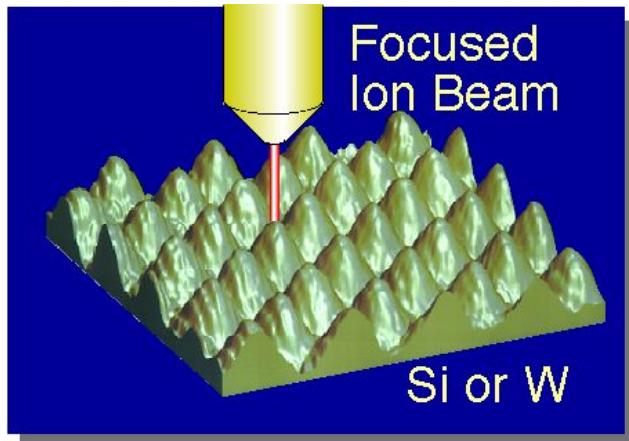


Friction coefficients measured in high vacuum

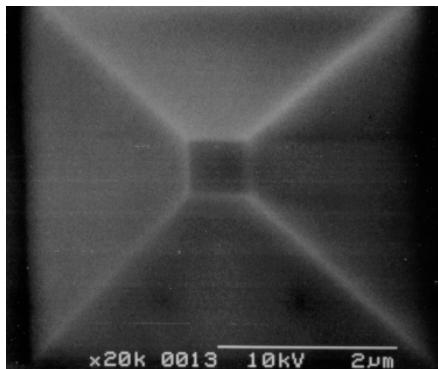


Lager difference in interatomic distance showed lower friction coefficient

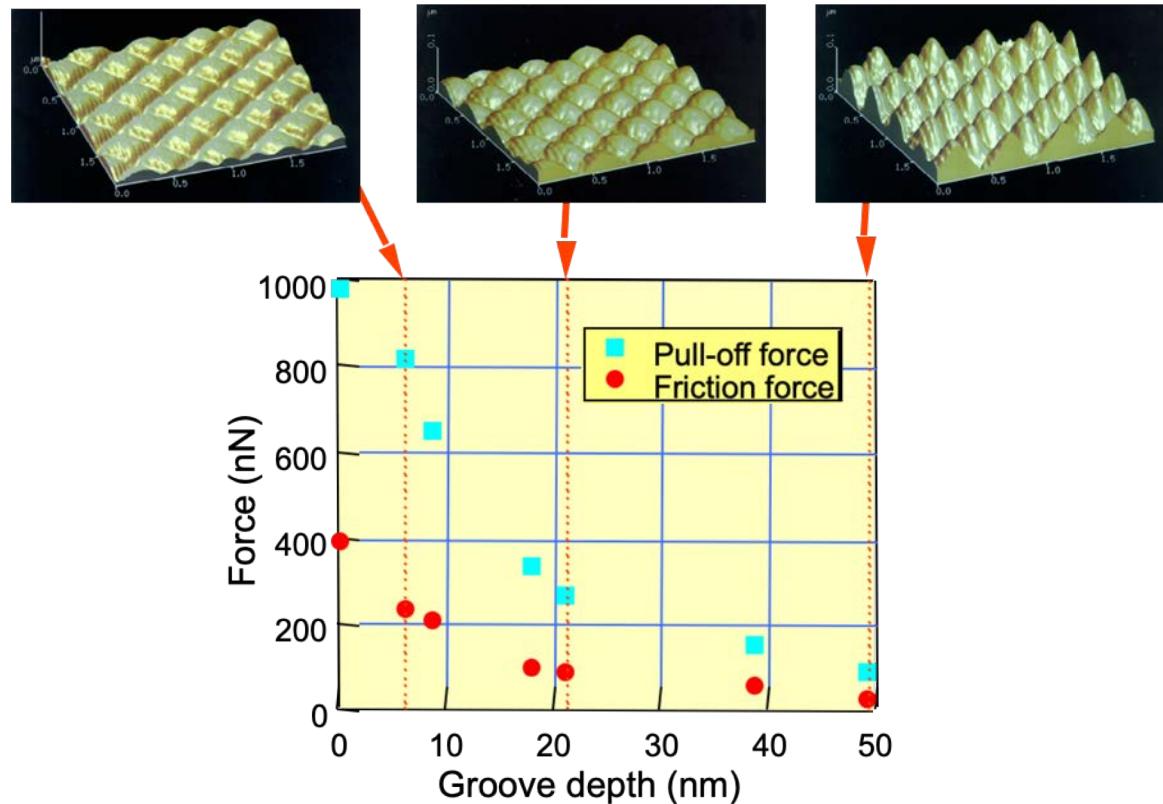
Fabricating nanoscale asperity arrays to control friction and adhesion force



FIB was used to create periodic asperity arrays

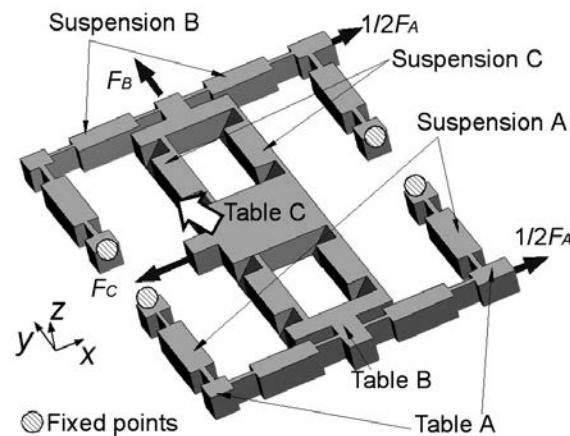
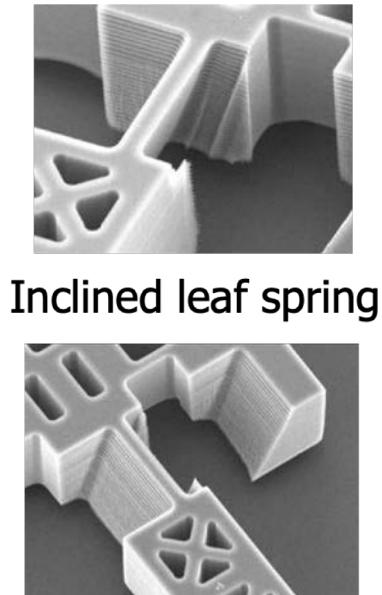
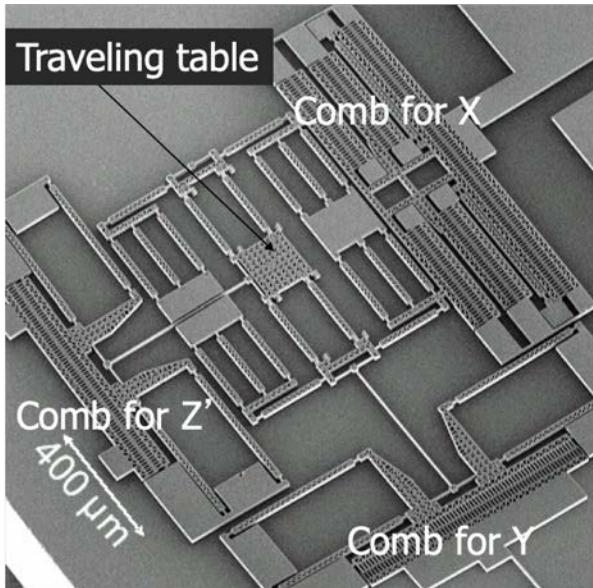


SEM image of scanning probe for AFM measurement

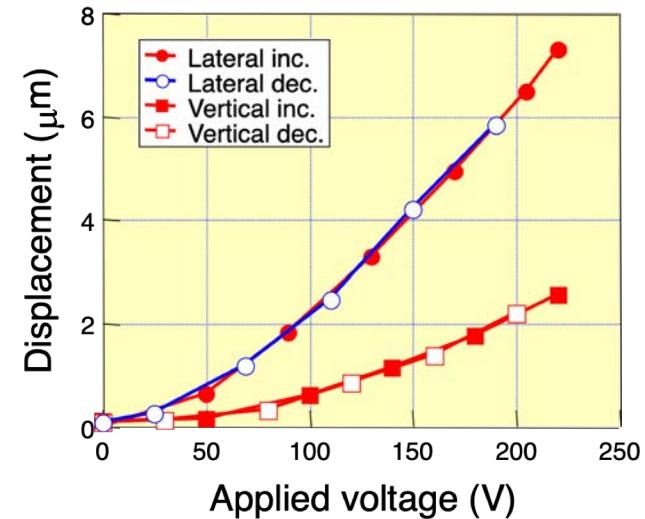


Friction and adhesion forces are reduced by applying periodic asperity array

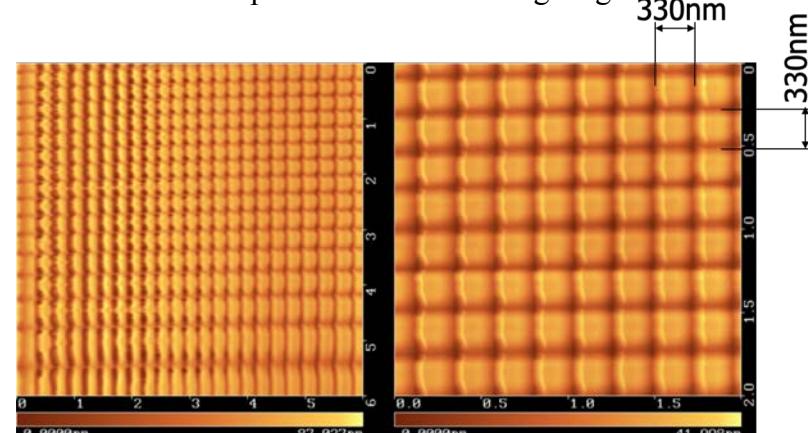
3次元マクロステージ



Inclined leaf springs in suspensions enable displacement in z-direction

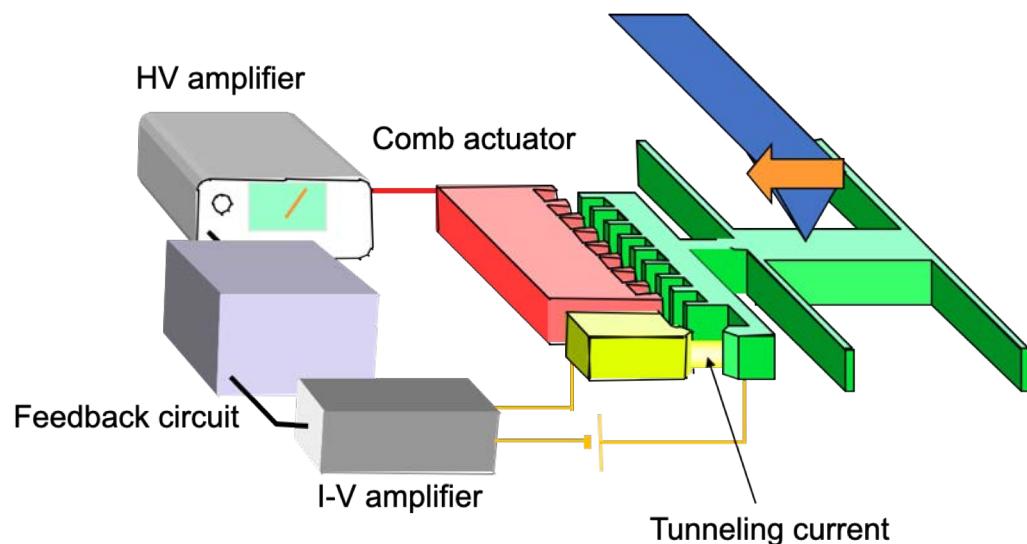
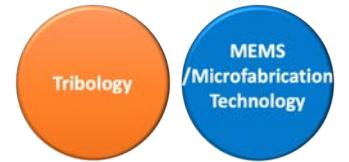


Displacement of traveling stage

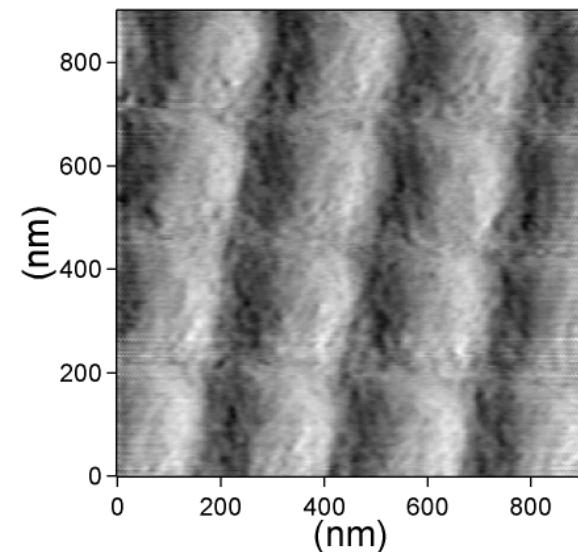


AFM image captured using 3D-microstage as scanning device

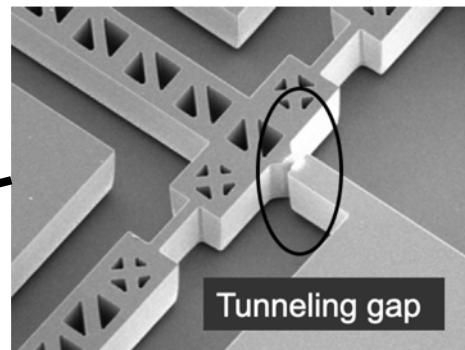
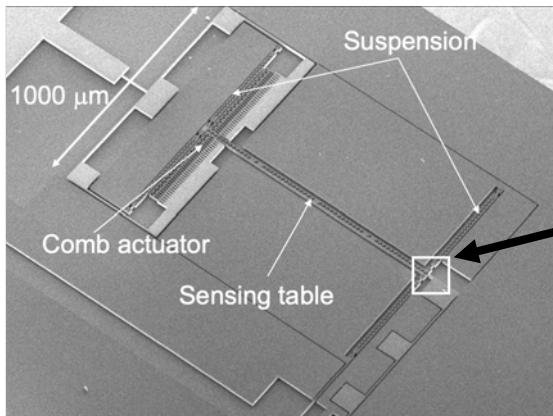
マイクロ水平力センサ



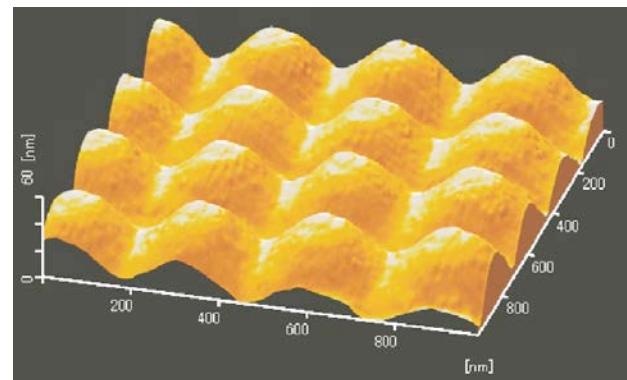
Using tunneling current to detect the displacement of force-sensing stage



LFM image obtained using MLFS

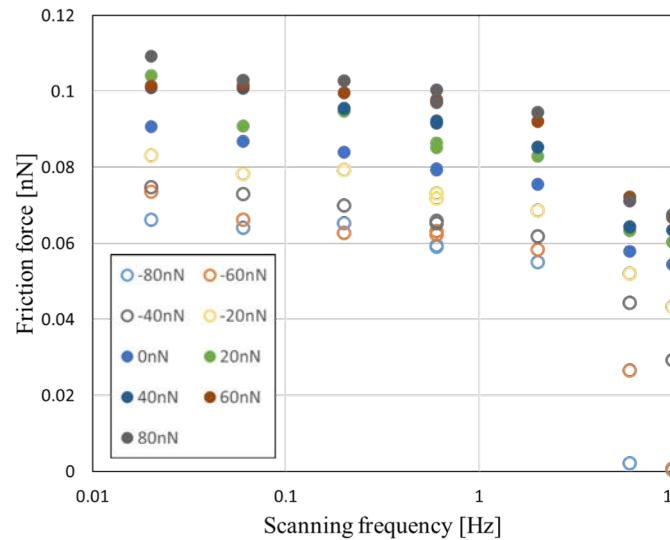
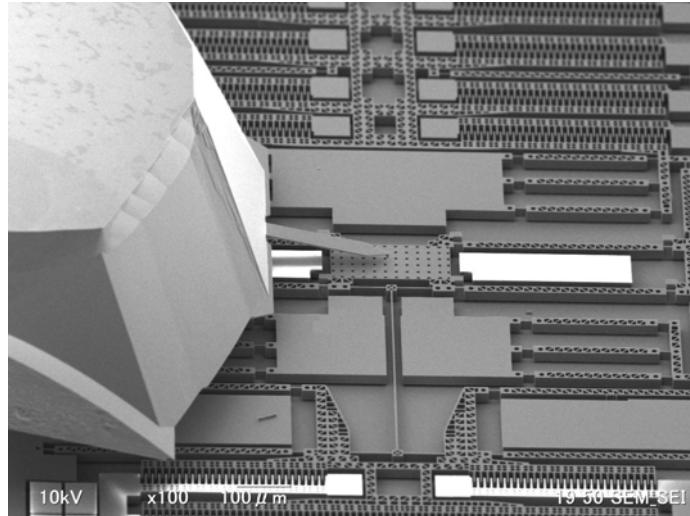


SEM image of whole device and tunneling gap

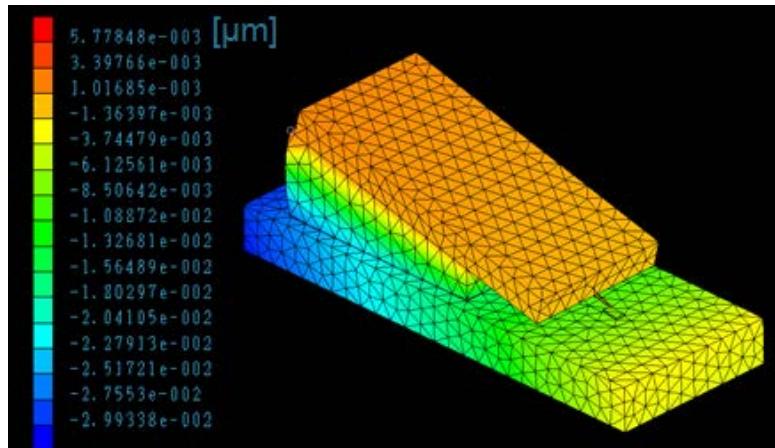


Testing area to measure LFM image

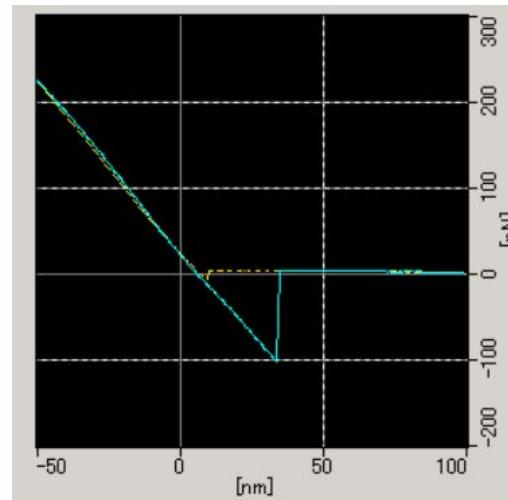
カンチレバー一体型μステージ



CI-3D-microstageで測定した摩擦力

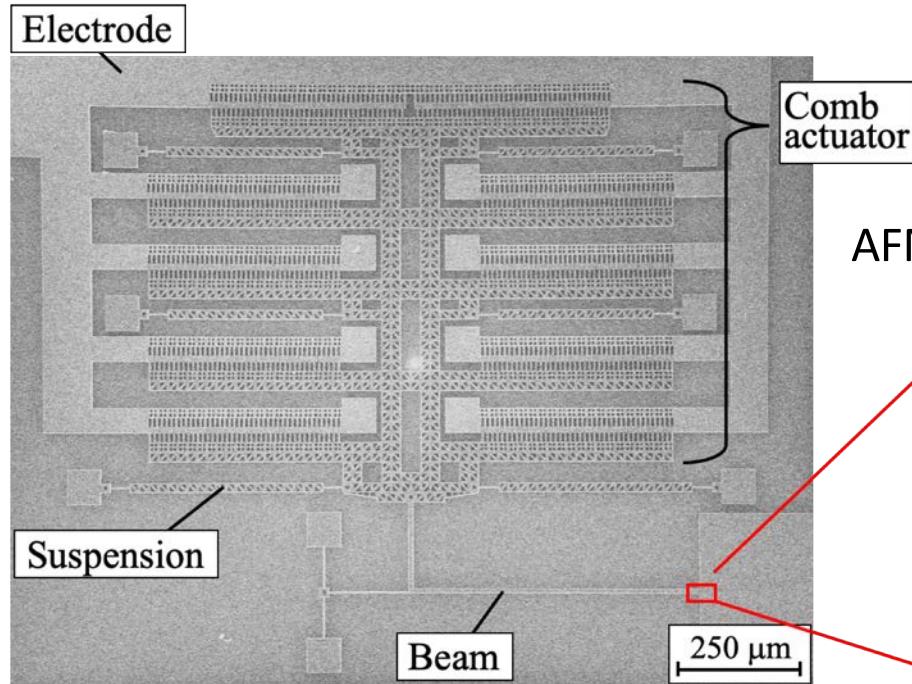


温度変化に対して荷重や位置制御が影響を受けない

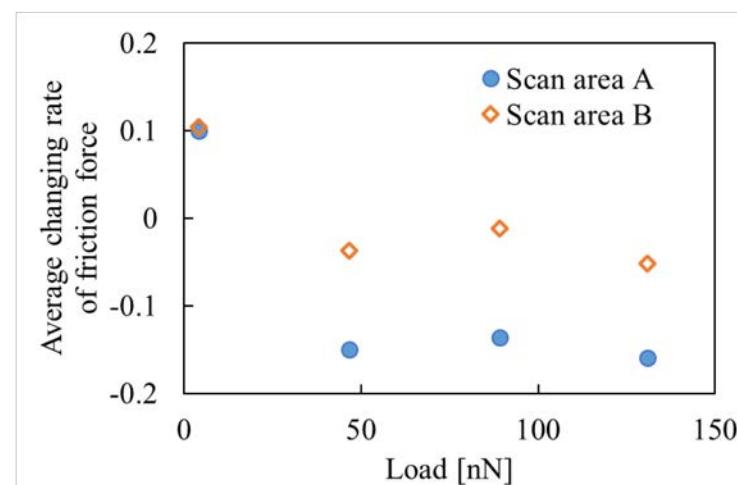
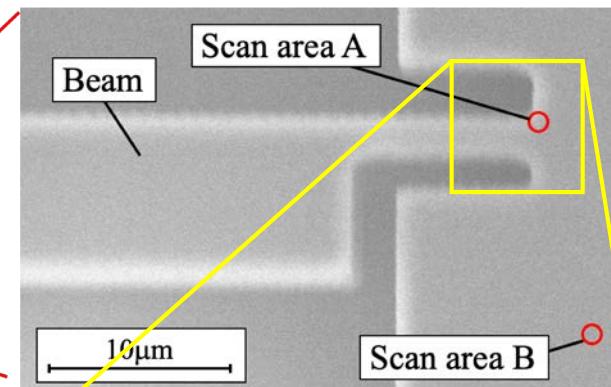


フォースカーブ測定がヒステリシスの影響を受けない

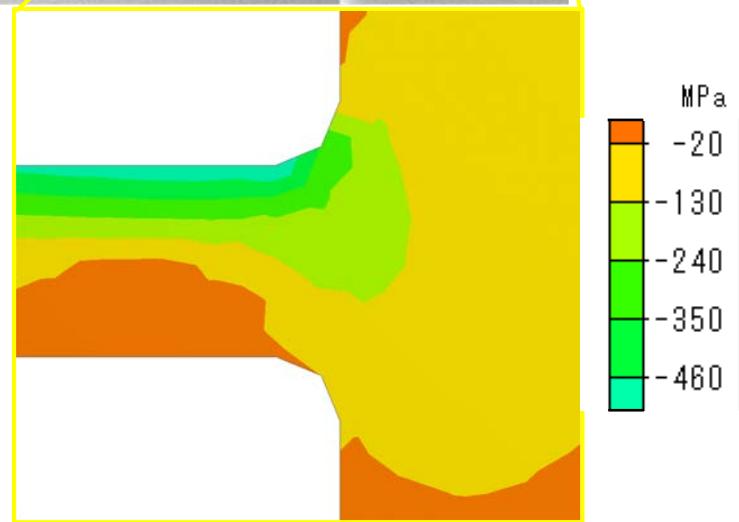
μ デバイスによる歪みと摩擦の関係



AFMに取り付けた応力集中 μ デバイス



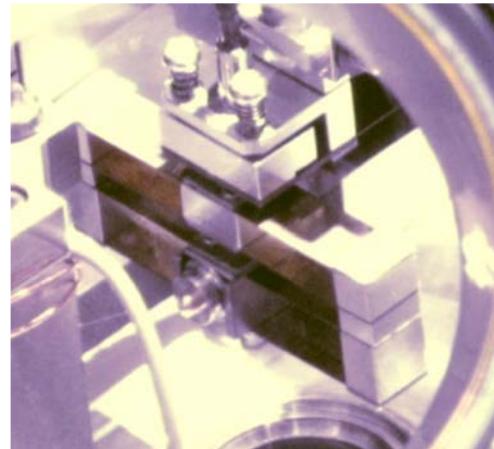
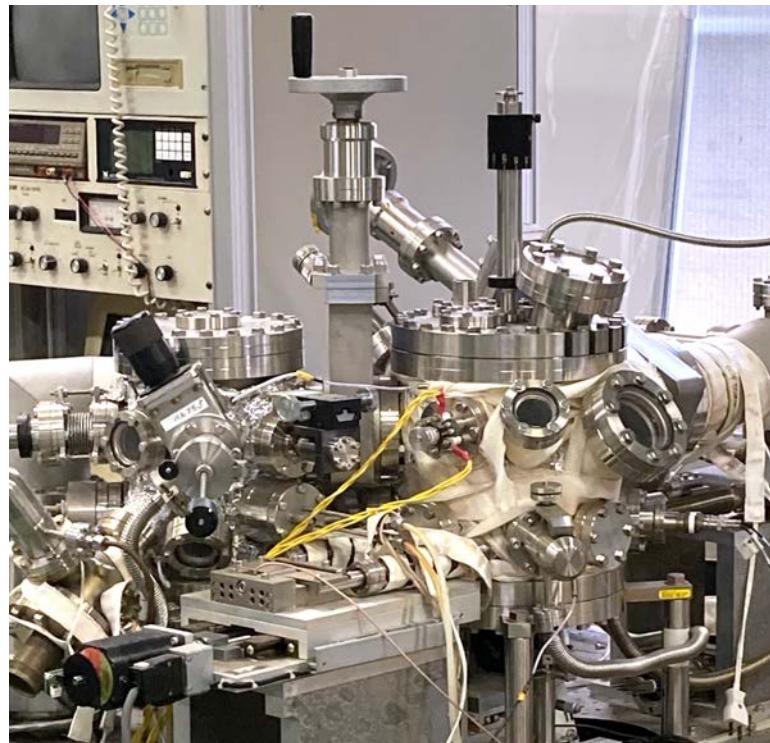
歪みにより15%程度摩擦力が低下した



FEM解析結果

代表的な研究設備

超高真空マイクロトライボロジー試験機



Specifications

Pressure: 10^{-7} Pa (Min.)

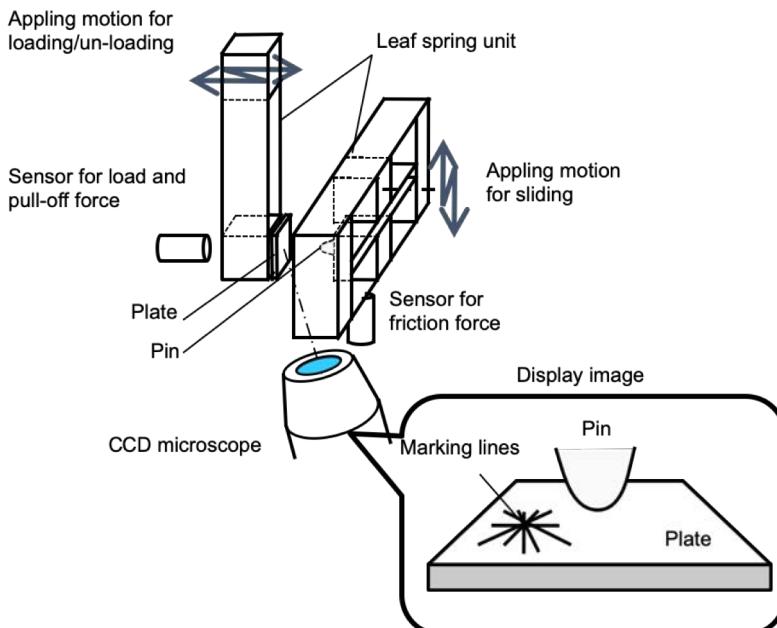
Force resolution: $\sim 0.1 \mu\text{N}$

Pull-off force measurement is possible

Sample heating in vacuum

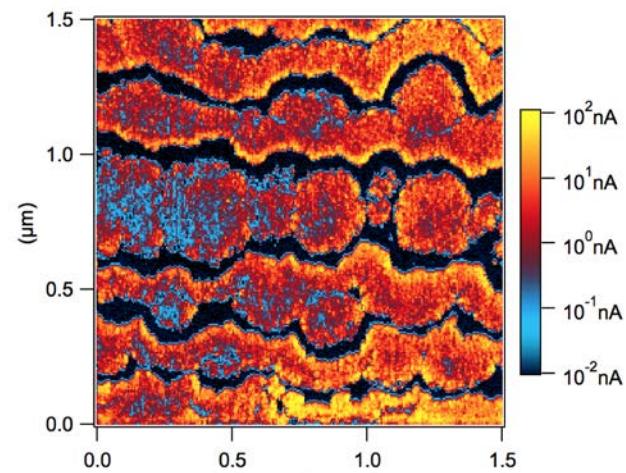
Sliding stroke: 0.3 mm (Max.)

Installed on Active vibration isolator



Samples can be changed and rotated in HV

高真空AFM (atomic force microscope)



電流分布測定（バイアス電圧を特注で
100Vまで増加させている）

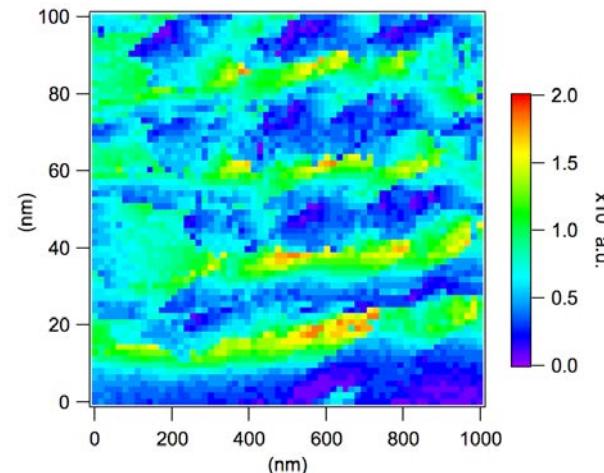
Specifications

Pressure: 10^{-5} Pa (min.)

Substrate temperature: -60 to 300 °C (800 °C)

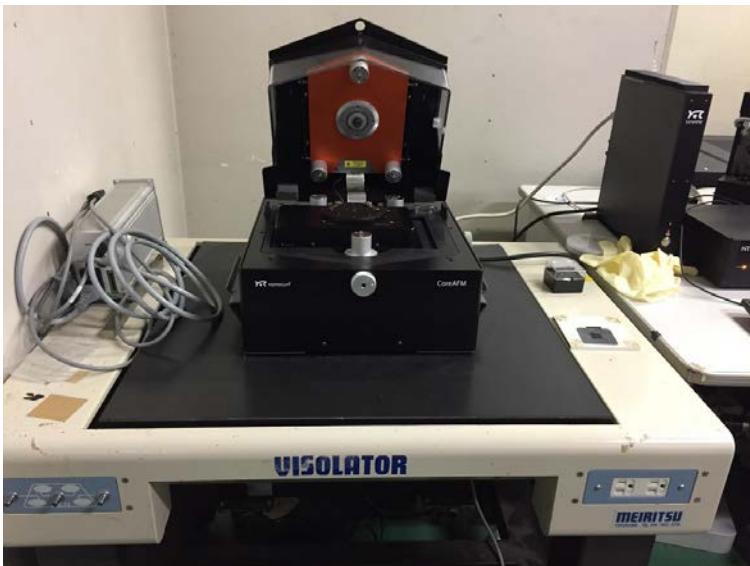
Current distribution: max. bias voltage of 100V

Pull-off force distribution: adjustable contact period
DFM, LM-LFM, LFM, etc.



高真空中で測定された引き離し力分布（接触時間
を0～1秒の間で調整できるように改修）

表面觀察装置



Nanosurf CoreAFM



Hitachi High-Tech Science AFM5010



Lasertec Corp. Optics Hybrid



Technex Lab Co. Tiny SEM

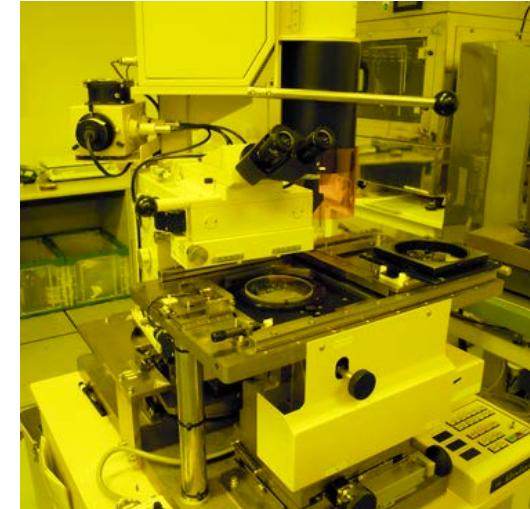
Fabrication facilities



RFスパッタ成膜装置



電気炉



両面マスクアライナ
4インチウェハ対応



研磨装置



小型スパッタ成膜装置



ダイシングソー